U.S. DEPARTMENT OF COMMERCE ATTY, DOCKET NO. Form PTO-1449 SERIAL NO. MI22-2416 PATENT AND TRADEWARK OFFICE 10/688,439 LIST OF ART CITED BY APPLICAN APPLICANT: Trung Tri Doan et al. (Use several sheets if necessary) **FILING DATE GROUP** October 16, 2003 2813 **U.S. PATENT DOCUMENTS** Subclass Filing Date If Appropriate Document Number Date Nama Class Initials 6,013,583 01/2000 Ajmera et al. AB AC AD Æ FOREIGN PATENT DOCUMENTS Document Date Country Class Subclass Translation Number Yes No 0817251 A1 11.06.97 EPO (IBM) US2004/021156 07.07.03 PCT (Micron - Internat'l Search Rep.) OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) Chen et al., Excimer Laser-Induced Ti Silicidation to Eliminate the Fine-Line Effect for Integrated Circuit Device Fabrication, J. ELECTROCHEM. Soc., Vol. 149, No. 11, pp. G609-G612 (2002). Nishiyama et al., Agglomeration Resistant Self-Aligned Silicide Process Using N₂ Implantation Into TiSi₂, JPN. J. APPL. PHYS., Vol. 36, Pt. 1, No. 6A, pp. 3639-3643 (June 1997). AO Wolf, Chapter 13: Polycides and Salicides of TiSix, CoSi2, and NiSi, SILICON PROCESSING FOR THE VLSI ERA, Vol. IV, pp. 603-604 (pre-2003). **EXAMINER** DATE CONSIDERED *EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not

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U.S. PATENT DOCUMENTS												
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03		*	2001/0041250 A1	11/2001	Werkhoven et al.							
		AB	2002/0000195 A1	01/2002	Bang et al.							
		AC	2002/0018849 A1	02/2002	George et al.	_						
		49	2003/0032281 A1	02/2003	Werkhoven et al.						·	
		¥	2003/0129826 A1	07/2003	Werkhoven et al.							
		AF	2004/0209484 A1	10/2004	Hill et al.				\exists			
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